AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions and listings of claims in the application:

1-64 (Cancelled)

- 65. (New) A lip makeup composition comprising at least one cosmetically acceptable organic liquid medium and at least one styrene-free film-forming block ethylenic polymer, wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.
- 66. (New) A lip makeup composition comprising at least one cosmetically acceptable organic liquid medium and at least one non-elastomeric film-forming block ethylenic polymer, wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.
- 67. (New) The lip makeup composition according to Claim 65 wherein the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 85%.
- 68. (New) The lip makeup composition according to Claim 67, wherein the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 95%.
- 69. (New) The lip makeup composition according to Claim 65 wherein the at least one block ethylenic polymer is not soluble at an active material content of at least 1% by weight in water or in a mixture of water and of linear or branched lower

monoalcohols containing from 2 to 5 carbon atoms, without pH modification, at room temperature (25°C).

- 70. (New) The lip makeup composition according to Claim 65 wherein the at least one block ethylenic polymer comprises at least one first block and at least one second block that have different glass transition temperatures (Tg), wherein the at least one first block and the at least one second block are connected together via at least one intermediate block comprising at least one constituent monomer of the at least one first block and at least one constituent monomer of the at least one second block.
- 71. (New) The lip makeup composition according to Claim 70, wherein the at least one first block and the at least second block are such that the difference between the glass transition temperatures (Tg) of the at least one first block and the at least one second block is greater than 10°C.
- 72. (New) The lip makeup composition according to Claim 71, wherein the at least one first block and the at least second block are such that the difference between the glass transition temperatures (Tg) of the at least one first block and the at least one second block is greater than 40°C.
- 73. (New) The lip makeup composition according to Claim 70, wherein the at least one intermediate block has a glass transition temperature that is between the glass transition temperatures of the at least one first block and the at least one second block.

- 74. (New) The lip makeup composition according to Claim 70, wherein the at least one first block and the at least one second block of the at least one block polymer are mutually incompatible.
- 75. (New) The lip makeup composition according to Claim 70, wherein the at least one block polymer has a polydispersity index of greater than 2.
- 76. (New) The lip makeup composition according to Claim 75, wherein the at least one block polymer has a polydispersity index ranging from 2.8 to 6.
- 77. (New) The lip makeup composition according to Claim 70, wherein the at least one first block of the at least one block polymer is chosen from:
- a) a block with a Tg of greater than or equal to 40°C,
- b) a block with a Tg of less than or equal to 20°C,
- c) a block with a Tg of between 20 and 40°C, and the at least one second block is chosen from a category a), b) or c) different from the at least one first block.
 - 78. (New) The lip makeup composition according to Claim 70, wherein the at least one block polymer comprises at least one first block with a glass transition temperature (Tg) of greater than or equal to 40°C and at least one second block with a glass transition temperature of less than or equal to 20°C.
 - 79. (New) The lip makeup composition according to Claim 78, wherein the proportion of the at least one first block ranges from 20% to 90% by weight of the polymer relative to the total weight of the composition.
 - 80. (New) The lip makeup composition according to Claim 79, wherein the proportion of the at least one first block ranges from 50% to 70% by weight of the polymer relative to the total weight of the composition.

- 81. (New) The lip makeup composition according to Claim 78, wherein the proportion of the at least one second block with a Tg of less than or equal to 20°C ranges from 5% to 75% by weight of the polymer relative to the total weight of the composition.
- 82. (New) The lip makeup composition according to Claim 81, wherein the proportion of the at least one second block with a Tg of less than or equal to 20°C ranges from 25% to 45% by weight of the polymer relative to the total weight of the composition.
- 83. (New) The lip makeup composition according to Claim 70, wherein the at least one block polymer comprises at least one first block with a glass transition temperature (Tg) of between 20 and 40°C and at least one second block with a glass transition temperature of less than or equal to 20°C or a glass transition temperature of greater than or equal to 40°C.
- 84. (New) The lip makeup composition according to Claim 83, wherein the proportion of the at least one first block with a Tg of between 20 and 40°C ranges from 10% to 85% by weight of the polymer relative to the total weight of the composition.
- 85. (New) The lip makeup composition according to Claim 84, wherein the proportion of the at least one first block with a Tg of between 20 and 40°C ranges from 50% to 70% by weight of the polymer relative to the total weight of the composition.
- 86. (New) The lip makeup composition according to Claim 83, wherein the at least one second block has a Tg of greater than or equal to 40°C.
- 87. (New) The lip makeup composition according to Claim 83, wherein the proportion of the at least one second block with a Tg of greater than or equal to 40°C

ranges from 10% to 85% by weight of the polymer relative to the total weight of the composition.

- 88. (New) The lip makeup composition according to Claim 87, wherein the proportion of the at least one second block with a Tg of greater than or equal to 40°C ranges from 30% to 70% by weight of the polymer relative to the total weight of the composition.
- 89. (New) The lip makeup composition according to Claim 83, wherein the at least one second block has a Tg of less than or equal to 20°C.
- 90. (New) The lip makeup composition according to Claim 77, wherein the proportion of the at least one block with a glass transition temperature of less than or equal to 20°C ranges from 20% to 90% by weight of the polymer relative to the total weight of the composition.
- 91. (New) The lip makeup composition according to Claim 90, wherein the proportion of the at least one block with a glass transition temperature of less than or equal to 20°C ranges from 50% to 70% by weight of the polymer relative to the total weight of the composition.
- 92. (New) The lip makeup composition according to Claim 77, wherein the at least one block with a Tg of greater than or equal to 40°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature of greater than or equal to 40°C.
- 93. (New) The lip makeup composition according to Claim 92, wherein the at least one block with a Tg of greater than or equal to 40°C is totally or partially derived

from at least one monomer whose homopolymer has a glass transition temperature ranging from 60°C to 120°C.

- 94. (New) The lip makeup composition according to Claim 92, wherein the at least one block with a Tg of greater than or equal to 40°C is a copolymer derived from at least one monomer whose homopolymer has a glass transition temperature of greater than or equal to 40°C.
- 95. (New) The lip makeup composition according to Claim 92, wherein the at least one monomer whose homopolymer has a glass transition temperature of greater than or equal to 40°C is chosen from the following monomers:
- methacrylates of formula $CH_2 = C(CH_3)$ -COOR₁ in which R_1 is a C_1 to C_4 linear or branched unsubstituted alkyl group or R_1 is a C_4 to C_{12} cycloalkyl group,
- acrylates of formula CH₂ = CH-COOR₂
 in which R₂ is a C₄ to C₁₂ cycloalkyl group
- (meth)acrylamides of formula:

$$CH_2 = C - CO - N$$
 R_8

in which R_7 and R_8 , which may be identical or different, are chosen from hydrogen atoms and C_1 to C_{12} linear or branched alkyl groups; or R_7 is hydrogen and R_8 is a 1,1-dimethyl-3-oxobutyl group, and R' is chosen from hydrogen an methyl,

- and mixtures thereof.
 - 96. (New) The lip makeup composition according to Claim 92, wherein the at least one monomer whose homopolymer has a glass transition temperature of greater

than or equal to 40°C is chosen from methyl methacrylate, isobutyl methacrylate and isobornyl (meth)acrylate, and mixtures thereof.

- 97. (New) The lip makeup composition according to Claim 77, wherein the at least one block with a Tg of greater than or equal to 40°C is a homopolymer.
- 98. (New) The lip makeup composition according to Claim 77, wherein the at least one block with a Tg of less than or equal to 20°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature of less than or equal to 20°C.
- 99. (New) The lip makeup composition according to Claim 98, wherein the at least one block with a Tg of less than or equal to 20°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature ranging from -50°C to 0°C.
- 100. (New) The lip makeup composition according to Claim 98, wherein the at least one monomer whose homopolymer has a glass transition temperature of less than or equal to 20°C is chosen from the following monomers:
- acrylates of formula CH_2 = $CHCOOR_3$, wherein R_3 is a linear or branched C_1 to C_{12} unsubstituted alkyl group, with the exception of the tert-butyl group, in which at least one hetero atom chosen from O, N and S is optionally intercalated;
- methacrylates of formula $CH_2 = C(CH_3)$ -COOR₄, R_4 is a linear or branched C_6 to C_{12} unsubstituted alkyl group, in which at least one hetero atom chosen from O, N and S is optionally intercalated;
- vinyl esters of formula R_5 -CO-O-CH = CH_2 in which R_5 is a linear or branched C_4 to C_{12} alkyl group,

- C₄ to C₁₂ alkyl vinyl ethers;
- N-(C₄ to C₁₂) alkyl acrylamides.
 - 101. (New) The lip makeup composition according to Claim 98, wherein the at least one monomer whose homopolymer has a glass transition temperature of less than or equal to 20°C is chosen from alkyl acrylates whose alkyl chain contains from 1 to 10 carbon atoms, with the exception of the tert-butyl group.
 - 102. (New) The lip makeup composition according to Claim 77, wherein the at least one block with a glass transition temperature of less than or equal to 20°C is a homopolymer.
 - 103. (New) The lip makeup composition according to Claim 77, wherein the at least one block with a Tg of between 20 and 40°C is totally or partially derived from at least one monomer whose homopolymer has a glass transition temperature ranging from 20 to 40°C.
 - 104. (New) The lip makeup composition according to Claim 77, wherein the at least one block with a Tg of between 20 and 40°C is a homopolymer of a monomer chosen from n-butyl methacrylate, cyclodecyl acrylate, neopentyl acrylate arid isodecylacrylamide.
 - 105. (New) The lip makeup composition according to Claim 77, wherein the at least one block with a Tg ranging from 20 to 40°C is a copolymer totally or partially derived from:
 - at least one monomer whose homopolymer has a Tg of greater than or equal to 40°C; and
 - at least one monomer whose homopolymer has a Tg of less than or equal to 20°C.

106. (New) The lip makeup composition according to Claim 77, wherein the at least one block with a Tg ranging from 20 to 40°C is totally or partially derived from at least one monomer chosen from methyl methacrylate, isobornyl (meth) acrylate, trifluoroethyl methacrylate, butyl acrylate and 2-ethylhexyl acrylate, and mixtures thereof.

107. (New) The lip makeup composition according to Claim 77, wherein the at least one first block and/or the at least one second block comprise(s) at least one additional monomer.

108. (New) The lip makeup composition according to Claim 107, wherein the at least one additional monomer is chosen from hydrophilic monomers, monomers containing ethylenic unsaturation comprising one or more silicon atoms, and mixtures thereof.

109. (New) The lip makeup composition according to Claim 107, wherein the at least one additional monomer is chosen from:

- ethylenically unsaturated monomers comprising at least one carboxylic or sulfonic acid function,
- methacrylates of formula CH₂ = C(CH₃)-COOR₆
 in which R₆ is a linear or branched C₁ to C₄ alkyl group, the said alkyl group being substituted with at least one substituent chosen from hydroxyl groups and halogen atoms,
- methacrylates of formula CH₂ = C(CH₃)-COOR₉,

 R_9 is a linear or branched C_6 to C_{12} alkyl group in which at least one hetero atoms chosen from O, N and S is (are) optionally intercalated, the said alkyl group being

substituted with at least one substituent chosen from hydroxyl groups and halogen atoms;

- acrylates of formula CH₂ = CHCOOR₁₀, wherein

 R_{10} is a linear or branched C_1 to C_{12} alkyl group substituted with at least one substituent chosen from hydroxyl groups and halogen atoms, or R_{10} is a C_1 to C_{12} alkyl-O-POE (polyoxyethylene) with repetition of the oxyethylene unit 5 to 30 times, or R_{10} is a polyoxyethylenated group comprising from 5 to 30 ethylene oxide units;

- ethylenically unsaturated monomers comprising at least one tertiary amine function,

and mixtures thereof.

- 110. (New) The lip makeup composition according to Claim 107, wherein the at least one additional monomer is chosen from acrylic acid, methacrylic acid and trifluoroethyl methacrylate, and mixtures thereof.
- 111. (New) The lip makeup composition according to Claim 107, wherein the at least one additional monomer is present in an amount ranging from 1% to 30% by weight relative to the total weight of the at least one first block and/or the at least one second block.
- 112. (New) The lip makeup composition according to Claim 77, wherein the at least one first block and the at least one second block comprise at least one monomer chosen from (meth)acrylic acid esters, and optionally at least one monomer chosen from (meth)acrylic acid, and mixtures thereof.
- 113. (New) The lip makeup composition according to Claim 77, wherein each of the at least one first block and the at least one second block is totally derived from at

least one monomer chosen from (meth)acrylic acid esters, and optionally from at least one monomer chosen from (meth)acrylic acid, and mixtures thereof.

- 114. (New) The lip makeup composition according to Claim 66, wherein the at least one block polymer is styrene-free.
- 115. (New) The lip makeup composition according to Claim 65, wherein the at least one block polymer has a weight-average mass (Mw) of less than or equal to 300,000.
- 116. (New) The lip makeup composition according to Claim 115, wherein the at least one block polymer has a weight-average mass (Mw) ranging from 45,000 to 150,000.
- 117. (New) The lip makeup composition according to Claim 65, wherein the at least one block polymer has a number-average mass (Mn) of less than or equal to 70,000.
- 118. (New) The lip makeup composition according to Claim 117, wherein the at least one block polymer has a number-average mass (Mn) ranging from 12,000 to 50,000.
- 119. (New) The lip makeup composition according to Claim 65, wherein the at least one block polymer is not an elastomer.
- 120. (New) The lip makeup composition according to Claim 65, wherein the at least one block polymer is present in an amount ranging from 0.1% to 60% by weight relative to the total weight of the composition.

- 121. (New) The lip makeup composition according to Claim 120, wherein the at least one block polymer is present in an amount ranging from 1% to 40% by weight relative to the total weight of the composition.
- 122. (New) The lip makeup composition according to Claim 65, further comprising at least one volatile oil.
- 123. (New) The lip makeup composition according to Claim 122, wherein the at least one volatile oil is chosen from octamethylcyclotetrasiloxane, decamethylcyclopentasiloxane, dodecamethylcyclohexasiloxane, heptamethylcyclohexasiloxane, octamethyltrisiloxane, decamethyltetrasiloxane, isododecane, isodecane and isohexadecane.
- 124. (New) The lip makeup composition according to Claim 122, wherein the at least one volatile oil is present in an amount ranging from 1% to 70% by weight relative to the total weight of the composition.
- 125. (New) The lip makeup composition according to Claim 124, wherein the at least one volatile oil is present in an amount ranging from 10% to 35% by weight relative to the total weight of the composition.
- 126. (New) The lip makeup composition according to Claim 65, further comprising a non-volatile oil.
- 127. (New) The lip makeup composition according to Claim 126, wherein the non-volatile oil is chosen from hydrocarbon-based non-volatile oils and silicone non-volatile oils.

128. (New) The lip makeup composition according to Claim 126, wherein the non-volatile oil is present in an amount ranging from 1% to 80% by weight relative to the total weight of the composition.

129. (New) The lip makeup composition according to Claim 128, wherein the non-volatile oil is present in an amount ranging from 20% to 50% by weight relative to the total weight of the composition.

130. (New) The lip makeup composition according to Claim 65, further comprising at least one fatty substance that is solid at room temperature, chosen from waxes, pasty fatty substances and gums, and mixtures thereof.

131. (New) The lip makeup composition according to Claim 65, wherein the lip makeup composition comprises from 0.1% to 50% by weight of waxes relative to the total weight of the composition.

132. (New) The lip makeup composition according to Claim 131, wherein the lip makeup composition comprises from 1% to 30% of waxes by weight relative to the total weight of the composition.

133. (New) The lip makeup composition according to Claim 65, further comprising at least one dyestuff.

134. (New) The lip makeup composition according to Claim 65, further comprising at least one cosmetic ingredient chosen from additional film-forming polymers, vitamins, thickeners, trace elements, softeners, sequestering agents, fragrances, acidifying or basifying agents, preserving agents, sunscreens, surfactants and antioxidants, and mixtures thereof.

135. (New) The lip makeup composition according to Claim 65, wherein the lip makeup composition is in the form of a paste or a stick.

136. (New) The lip makeup composition according to Claim 65, wherein the lip makeup composition is in anhydrous form.

137. (New) A cosmetic assembly comprising:

- a) at least one container delimiting at least one compartment, the at least one container being closed by a closing member; and
- b) a lip makeup composition placed inside the at least one compartment, wherein the lip makeup composition comprises:

at least one cosmetically acceptable organic liquid medium, and at least one styrene-free film-forming block ethylenic polymer,

wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.

138. (New) A cosmetic assembly comprising:

- a) at least one container delimiting at least one compartment, the at least one container being closed by a closing member; and
- b) a lip makeup composition placed inside the at least one compartment, wherein the lip makeup composition comprises:

at least one cosmetically acceptable organic liquid medium, and at least one non-elastomeric film-forming block ethylenic polymer,

wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.

- 139. (New) The cosmetic assembly according to Claim 137, wherein the at least one container is at least partially formed from at least one thermoplastic material.
- 140. (New) The cosmetic assembly according to Claim 137, wherein the at least one container is at least partially formed from at least one non-thermoplastic material.
- 141. (New) The cosmetic assembly according to Claim 137, wherein in the closed position of the at least one container, the closing member is screwed onto the container.
- 142. (New) The cosmetic assembly according to Claim 137, wherein in the closed position of the at least one container, the closing member is coupled to the at least one container in a manner other than by screwing, including click-fastening, bonding or welding.
- 143. (New) A cosmetic process for making up the lips, comprising applying a lip makeup composition to the lips, wherein the lip makeup composition comprises:

at least one cosmetically acceptable organic liquid medium, and at least one styrene-free film-forming block ethylenic polymer,

wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.

144. (New) A cosmetic process for making up the lips, comprising applying a lip makeup composition to the lips wherein the lip makeup composition comprises:

at least one cosmetically acceptable organic liquid medium, and at least one non-elastomeric film-forming block ethylenic polymer,

wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.

145. (New) A method for obtaining a lip makeup composition that provides a deposit on the lips that has good resistance, said method comprising including in the lip makeup composition at least one cosmetically acceptable organic liquid medium, and

at least one styrene-free film-forming block ethylenic polymer,

wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.

146. (New) A method for obtaining a lip makeup composition that provides a deposit on the lips that has good resistance, said method comprising including in the lip makeup composition at least one cosmetically acceptable organic liquid medium, and

at least one non-elastomeric film-forming block ethylenic polymer,

wherein the at least one block ethylenic polymer is such that, when it is present in a sufficient amount in the composition, the lip makeup composition can form a deposit that has a resistive index of greater than or equal to 80%.